

LAW OFFICES

SAWYER AND ASSOCIATES

INTELLECTUAL PROPERTY LAW

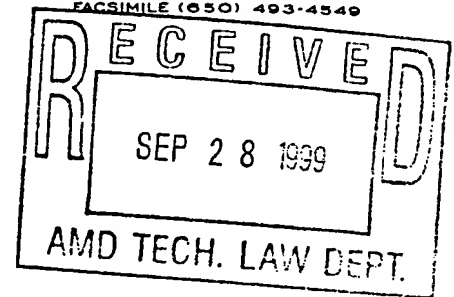
JOSEPH A. SAWYER, JR.

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September 27, 1999

VIA FEDERAL EXPRESS

Ms. Shelly Garrett  
Advanced Micro Devices, Inc.  
1160 Kern, M/S 68  
Sunnyvale, CA 94086

Re: New United States Patent Application  
Title: METHOD AND SYSTEM FOR REDUCING ARC LAYER  
REMOVAL DURING REMOVAL OF PHOTORESIST  
Your Reference: D900  
Our Reference: 1368P

Dear Shelly:

Enclosed is a final draft of the above-identified patent application including claims and drawings. Also enclosed are the formal papers required to complete the filing of this application. Kindly obtain the appropriate signatures and return the executed documents to our office as soon as possible so that we may file this application in a timely manner.

Thank you for your assistance in this matter. If you have any questions, please do not hesitate to contact our office.

Very truly yours,

*Janyce R. Mitchell*  
FOR:

Janyce R. Mitchell

Enclosures  
AMD\092799.1368P

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August 13, 1999

VIA FACSIMILEMs. Marina Platt  
Advanced Micro Devices, Inc.  
One AMD Place  
Sunnyvale, CA 94088Re: United States Patent Application  
Title: METHOD AND SYSTEM FOR REDUCING  
ARC LAYER REMOVAL DURING REMOVAL  
OF PHOTORESIST  
Your Reference: D900 -  
Our Reference: 1368PRECEIVED  
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Dear Marina:

Please find attached a first draft of the above-identified patent application including claims and informal drawings. Please carefully review the draft to ensure that the application, including the specification, claims and drawings, completely and accurately describes and claims your invention. Any additions or changes should be made directly on the draft application, and the corresponding pages should be returned to me as soon as possible.

The most pertinent prior art of which we are aware has been cited in the patent application itself. If you are aware of any additional or more pertinent prior art or other material information that should be called to the attention of the Patent Office, please insert reference to it directly on the draft application.

If you have any questions, please do not hesitate to contact me.

Very truly yours,

  
Janyce R. MitchellEnclosures  
AMD\081599.1368P

SAWYER AND ASSOCIATES

INTELLECTUAL PROPERTY LAW

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September 22, 1999

VIA FACSIMILE

Ms. Marina V. Plat  
Advanced Micro Devices, Inc.  
One AMD Place  
Sunnyvale, CA 94088

Re: United States Patent Application  
Title: METHOD AND SYSTEM FOR REDUCING ARC LAYER  
REMOVAL DURING REMOVAL OF PHOTORESIST  
Your Reference: D900  
Our Reference: 1368P

Dear Ms. Plat:

Attached for your review is a second draft of the subject application with revisions appearing in bold print. Please carefully review the draft to ensure that the application, including the specification, claims and the drawings, completely and accurately describes and claims your invention. Any additions or changes should be made directly on the draft application, and the corresponding pages should be returned to me as soon as possible.

The most pertinent prior art of which we are aware has been cited in the patent application itself. If you are aware of any additional or more pertinent prior art or other material information that should be called to the attention of the Patent Office, please insert reference to it directly on the draft application.

If you have any questions, please do not hesitate to contact me.

Very truly yours,

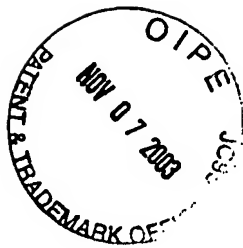
*J. Tandra*  
FOR

Janyce R. Mitchell

Attachments  
AMD092299.1368P

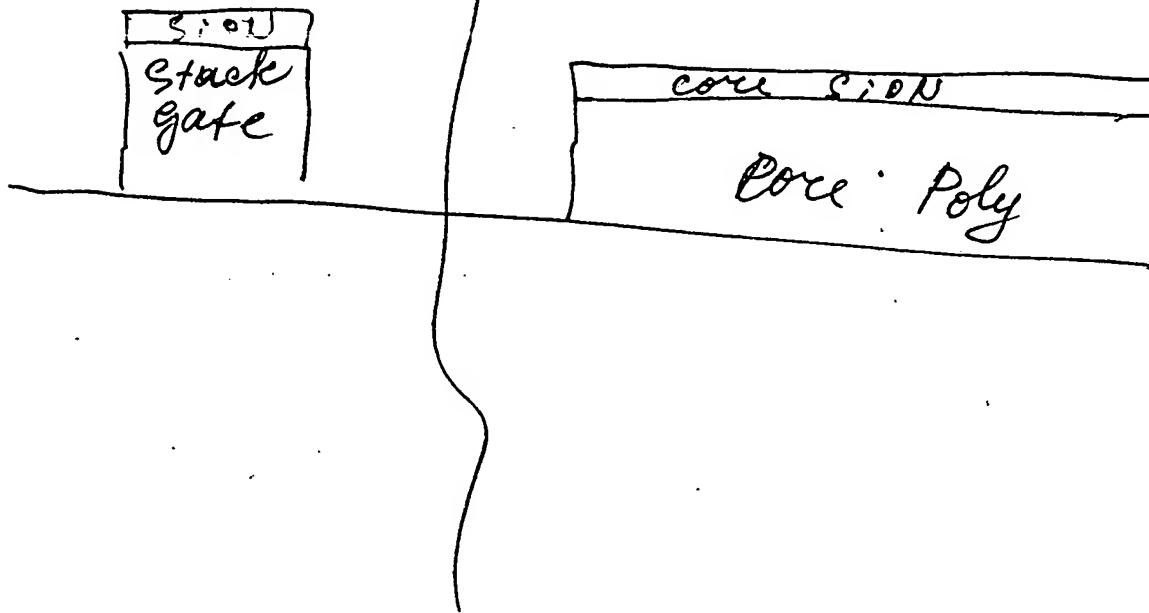
cc: Barbara deRuyter (w/out enclosure)

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Stack gate

Core gate



Layer there  
SiO<sub>2</sub> gets depleted  
— Due to  
removal

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